

Title (en)

HIGH QUALITY MATRIX PRINTING PROCESS AND SYSTEM USING ELECTROPHOTOGRAPHIC PRINTING EQUIPMENT

Title (de)

VERFAHREN UND ANORDNUNG ZUR ERZEUGUNG VON RASTERDRUCK HOHER QUALITÄT MIT EINER ELEKTROFOTOGRAPHISCHEN DRUCKEINRICHTUNG

Title (fr)

PROCEDE ET DISPOSITIF D'IMPRESSION PAR POINTS DE HAUTE QUALITE AU MOYEN D'UN SYSTEME D'IMPRESSION ELECTROPHOTOGRAPHIQUE

Publication

EP 0683954 B1 19980610 (DE)

Application

EP 94906221 A 19940204

Priority

- EP 94906221 A 19940204
- EP 9400323 W 19940204
- EP 93102070 A 19930210

Abstract (en)

[origin: US5767888A] PCT No. PCT/EP94/00323 Sec. 371 Date Aug. 10, 1995 Sec. 102(e) Date Aug. 10, 1995 PCT Filed Feb. 4, 1994 PCT Pub. No. WO94/18786 PCT Pub. Date Aug. 18, 1994An electrophotographic process and arrangement for generates a macro-charge zone inkable by toner applicators and delimited by an inking limit (EG) having an adjustable contour on a photoconductor of a printing or copying machine, using at least one exposure-variable and position-variable controllable light source (LED), such as an LED comb or laser. By controlling the exposure of the light source and its radiation position on the photoconductor and by controlling a bias voltage (UB) which can be applied between photoconductor and toner applicator, an electrostatic potential relief (UR) made up of individual adjacent micro-charge zones (UM) of exposure-dependent size is generated on the photoconductor and the inking limit (EG) is defined, the contour of the inking limit being determined by the bias voltage level (UB) on the potential relief (UR). The process and the arrangement allow an offset-like printing quality to be obtained, both with respect to the generation of half-tone images and of lines and characters.

IPC 1-7

H04N 1/40

IPC 8 full level

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CPC (source: EP US)

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